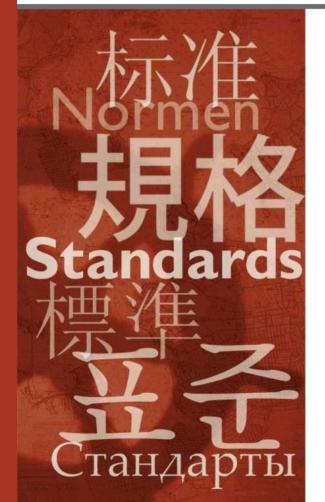
Portland October 16, 2006 Workshop: Electrostatic Issues in Semiconductor Manufacturing



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CD with presentations available



Agenda

1:30 – 1:40 WELCOME AND INTRODUCTION – A. STEINMAN 1:40 - 2:15A. STEINMAN (MKS, Ion Systems) Overview of Electrostatic Recommendations in Updated E78, E129 and the ITRS 2005 2:15 - 2:50J.A. MONTOYA (Intel Corporation) **Electrostatic Charge Control Considerations** 2:50 - 3:20M. HOGSETT (NOVX) -**Electrostatic Risk – Decisions Under Uncertainty** 3:20 - 3:40**QUESTIONS and BREAK** L. LEVIT (MKS, Ion Systems) – Measurement Protocols for 3:40 - 4:10Quantifying the Effects of Electrostatic Attraction on Microcontamination in a Semiconductor Fab 4:10 - 4:40M. NORAS (TREK) – Electrostatic Measurement Issues and **SEMI E43** 4:40 - 5:10V. KRAZ (3M/Credence Technology) **Electromagnetic Compatibility Issues and SEMI E33 ALL - PANEL** 5:10 - 5:30

Thoughts for Today

- Physics is the same everywhere. We have no static problems in our factory????
- Denial costs a lot of money.
- As devices become smaller in size, faster in operating speed, and more complex, the static problems will become worse.
- The day we hit a technology barrier in semiconductor production due to static charge is coming closer. HDD and FPD production have already hit this barrier.

